

<p>Form PTO-1449</p> <p>ON INFORMATION DISCLOSURE CITATION IN AN APPLICATION</p> <p>DEC 10 2003 (Use several sheets if necessary)</p>				Document Number (Opinion)	TSMC-01-1247	Application Number	10/657,505
				Applicant	Chi-i-Ming Wu et al.		
				Filing Date	09/08/03		Drawn At U.S.
U.S. PATENT DOCUMENTS							
DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	SEARCH DATE IF APPROPRIATE		
5 919 887 1	12/7/99	Urabe	257	754	2/20/98		
6 037 252 3	3/14/00	Hillman et al.	438	637	11/5/97		
6 203 613 3	3/20/01	Gates et al.	117	104	10/19/99		
6 270 572 8	7/1/01	Kim et al.	117	93	8/9/99		
6 468 924 1	10/22/02	Lee et al.	438	763	5/31/01		
6 174 809 1	1/16/01	Kang et al.	438	682	12/15/98		
6 399 491 6	4/6/02	Jeon et al.	438	680	4/6/01		
6 139 700 10	10/31/00	Kang et al.	204	192.17	9/30/98		
FOREIGN PATENT DOCUMENTS							
DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES <input checked="" type="checkbox"/> NO <input type="checkbox"/>		
OTHER DOCUMENTS (Including Author, Title, Date, Page No., Etc.)							
<p>Patent Application TSMC-01-1248, Serial # 10/653,852, File Date 09/03/03, assigned to a common assignee, "Method of Multi-Element Compound Deposition by Atomic Layer Deposition for IC Barrier Layer Applications".</p>							
EXAMINER				DATE CONSIDERED			
Jeff M. Kennedy				October 20, 2005			

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.